

L Number	Hits	Search Text	DB	Time stamp
1	2155	(438/624,633,692).CCLS.	USPAT	2002/10/18 13:52
2	1295	(257/635,637-644,760).CCLS.	USPAT	2002/10/18 13:53
3	798	((438/624,633,692).CCLS.) ((257/635,637-644,760).CCLS.)) and (dielectric adj constant low\$1k)	USPAT	2002/10/18 13:55
4	605	((438/624,633,692).CCLS.) ((257/635,637-644,760).CCLS.)) and (dielectric adj constant low\$1k)) and ((stack\$3 layer\$3 combination combin\$3) near4 (stopper\$1 resist\$3 prevent\$3 protect\$3 barrier\$1))	USPAT	2002/10/18 14:16
5	20	((438/624,633,692).CCLS.) ((257/635,637-644,760).CCLS.)) and (dielectric adj constant low\$1k)) and ((stack\$3 layer\$3 combination combin\$3) near4 (stopper\$1 resist\$3 prevent\$3 protect\$3 barrier\$1)) and ((nitrogen n2 n?sub.2 nh3 ammonia nh?sub.3) near15 (stopper\$1 resist\$3 prevent\$3 protect\$3 barrier\$1) same diffus\$3)	USPAT	2002/10/18 14:03
6	585	((438/624,633,692).CCLS.) ((257/635,637-644,760).CCLS.)) and (dielectric adj constant low\$1k)) and ((stack\$3 layer\$3 combination combin\$3) near4 (stopper\$1 resist\$3 prevent\$3 protect\$3 barrier\$1)) not (((438/624,633,692).CCLS.) ((257/635,637-644,760).CCLS.)) and (dielectric adj constant low\$1k)) and ((stack\$3 layer\$3 combination combin\$3) near4 (stopper\$1 resist\$3 prevent\$3 protect\$3 barrier\$1)) and ((nitrogen n2 n?sub.2 nh3 ammonia nh?sub.3) near15 (stopper\$1 resist\$3 prevent\$3 protect\$3 barrier\$1) same diffus\$3))	USPAT	2002/10/18 14:17
-	20510	((etch\$3 polish\$3) adj (stop\$4 resist\$3 retard\$5 prevent\$3)) cap\$1 capping mask\$1 barrier) near3 (layers layered stack\$3)	USPAT	2002/10/18 11:58
-	735	((etch\$3 polish\$3) adj (stop\$4 resist\$3 retard\$5 prevent\$3)) cap\$1 capping mask\$1 barrier) near3 (layers layered stack\$3)) and ((etch\$3 polish\$3) adj (stop\$4 resist\$3 retard\$5 prevent\$3)) cap\$1 capping mask\$1 barrier) near15 (nitrogen "N-H" nh3 nh?sub.3 nSub.s n2)	USPAT	2002/10/18 12:04
-	96	((etch\$3 polish\$3) adj (stop\$4 resist\$3 retard\$5 prevent\$3)) cap\$1 capping mask\$1 barrier) near3 (layers layered stack\$3)) and ((etch\$3 polish\$3) adj (stop\$4 resist\$3 retard\$5 prevent\$3)) cap\$1 capping mask\$1 barrier) near15 (nitrogen "N-H" nh3 nh?sub.3 nSub.s n2)) and (((etch\$3 polish\$3) adj (stop\$4 resist\$3 retard\$5 prevent\$3)) cap\$1 capping mask\$1 barrier) near2 (layered stack\$3))	USPAT	2002/10/18 12:22
-	4	(low near2 dielectric adj (constant k)) same (((etch\$3 polish\$3) adj (stop\$4 resist\$3 retard\$5 prevent\$3)) cap\$1 capping mask\$1 barrier) near2 (layered stack\$3))	USPAT	2002/10/18 13:44